	Ty pe	Hits	Search Text	DBs	Time Stamp	Comm ents	Error Definit ion	Errors	Ref#
1	BR S	4	("4874401" "493331 4" "5603892" "6560 839").PN.	USPAT; EPO; JPO	2005/05/ 13 14:08				S1
2	BR S	196	theriault.in.	USPAT; EPO; JPO	2005/03/ 23 18:05				S2
3	BR S	4	theriault-martin.in.	USPAT; EPO; JPO	2005/03/ 23 18:06				S3
4	BR S	8	S1 S3	USPAT; EPO; JPO	2005/03/ 23 18:06				S4
5	BR S	0	S4 and dessica\$3	USPAT; EPO; JPO	2005/03/ 23 18:07				S5
6	BR S		("4874401" "493331 4" "5603892" "6560 839").PN.	USPAT; EPO; JPO	2005/03/ 24 10:23				S6
7	BR S	4	theriault-martin.in.	USPAT; EPO; JPO	2005/03/ 24 10:23				S7
8	BR S	8	S6 S7	USPAT; EPO; JPO	2005/03/ 24 10:23				S8
9	BR S	5	S8 and nitrogen	USPAT; EPO; JPO	2005/03/ 24 10:30				S9
10	BR S	1	S9 and humidity	USPAT; EPO; JPO	2005/03/ 24 10:23				S10
11	BR S	119	, ,	USPAT; EPO; JPO	2005/03/ 24 10:30				S11
12	BR S	30	S11 and (membrane with nitrogen)	USPAT; EPO; JPO	2005/03/ 24 16:05				S12
13	BR S	119	,	USPAT; EPO; JPO	2005/03/ 24 14:27				S13
14	BR S	0	jp-9109387-\$.did.	USPAT; EPO; JPO	2005/03/ 24 16:06				S14

	Ty pe	Hits	Search Text	DBs	Time Stamp	Comm ents	Error Definit ion	Errors	Ref#
	BR S		jp-3332687-\$.did.	USPAT; EPO; JPO	2005/03/ 24 16:08				S15
16	BR S	0	"3332687"	ЛО	2005/03/ 24 16:09				S16
17	2		@pd="19970415"	ЉО	2005/03/ 24 16:09				S17
	BR S		S17 and wall	JPO	2005/03/ 24 16:09				S18
19	BR S	7	S18 and bar	JPO	2005/03/ 24 16:13				S19
20	BR S	0	gb-2235115-\$.did.	JPO	2005/03/ 24 16:13				S20
21	S	U	gb-02235115-\$.did.	JPO	2005/03/ 24 16:13				S21
22	BR S	0	uk-2235115-\$.did.	JPO	2005/03/ 24 16:13				S22
23	BR S	1	gb-2235115-\$.did.	DERWEN T	2005/03/ 24 16:13				S23
24	BR S	1	"6655168".pn.	1	2005/05/ 13 14:11				S24
25	BR S	1	S24 and nitrogen	1	2005/05/ 13 14:11				S25
26	BR S	0	S24 and deiscca\$5	USPAT; EPO; JPO	2005/05/ 13 14:11				S26
27	BR S	0	S24 and desicca\$5	USPAT; EPO; JPO	2005/05/ 13 14:12				S27
28	S	8140	desiccator	USPAT; EPO; JPO	2005/05/ 13 14:12				S28
29	BR S	92	(desiccator with membrane)	1	2005/05/ 13 14:12				S29

	Document ID	Issue Date	Title	Current OR	Current XRef	Inventor
1	US 5740845 A	1998	Sealable, transportable container having a breather assembly	141/292	141/98; 206/710; 414/217; 414/217.1; 414/411; 414/940	Bonora; Anthony C. et al.
2	US 5735961 A	1998 0407	Semiconductor fabricating apparatus, method for controlling oxygen concentration within load-lock chamber and method for generating native oxide		118/715; 118/719; 414/937; 414/939; 432/241	Shimada; Masakazu
3	US 5611452 A	1	Sealable transportable container having improved liner	220/378	220/681;	Bonora; Anthony C. et al.
4	US 5575081 A	1110	Device for transporting magazines for molding wafer-shaped objects	34/218	34/222; 34/224; 414/217; 414/217.1; 414/940	Ludwig; Joachim
5	US 5536320 A	1996 0716	Processing apparatus	118/719	414/938;	Ushikawa; Harunori et al.

	Document ID	Issue Date	Title	Current OR	Current XRef	Inventor
6		ł	Mechanical interface wafer container	206/711	141/98; 206/454; 220/323; 414/217; 414/217.1; 414/292; 414/940	Williams; Randall S. e al.
7	US 5469963 A		Sealable transportable container having improved liner	17Uh/7U9	206/454; 361/212	Bonora; Anthony C. et al.
8	US 5433574 A		Gas purge unit for a portable container	414/217	414/416.0 3; 414/940	Kawano; Hitoshi et al
9	US 5373806 A	1994 1220	Particulate-free epitaxial process	11 I // I Uh	·	Logar; Roger E.
10	US 5354198 A	1	Movable cantilevered purge system	432/5	432/11; 432/152; 432/253	Yates; Cleon R.
11			Closed container to be used in a clean room	206/213. 1	118/500; 141/67; 141/98; 206/454; 211/41.18; 414/935	Yamashita; Teppei et al.
12	US 5277579 A	1994 0111	Wafers transferring method in vertical type heat treatment apparatus and the vertical type heat treatment apparatus provided with a wafers transferring system	432/5	414/217; 414/937; 414/939; 414/940; 432/241; 432/6	Takanabe; Eiichiro

	Document ID	Issue Date	Title	Current OR	Current XRef	Inventor
13	US 5255783 A	1993 1026	Evacuated wafer container	206/711	141/65; 141/98; 206/454; 206/524.8	Goodman; John B. et al.
14	US 5252133 A	1012	Vertically oriented CVD apparatus including gas inlet tube having gas injection holes	1	118/715; 118/724; 118/730	Miyazaki; Shinji et al.
15	US 5169272 A	1992 1208	Method and apparatus for transferring articles between two controlled environments	414/217. 1	414/422	Bonora; Anthony C. et al.
16	US 5032545 A		Process for preventing a native oxide from forming on the surface of a semiconductor material and integrated circuit capacitors produced thereby	438/762	257/E21.2 26; 257/E21.2 93; 257/E21.3 96; 438/396; 438/775; 438/791; 438/906; 438/974	Doan; Trung T. et al.
17	US 4957781 A	1990 0918	Processing apparatus	427/255. 26	118/715; 118/725; 118/728; 219/385; 219/390; 414/217; 427/248.1	Kanegae; Masatomo e al.

	Document	Issue	Title	Current	l .	Inventor
18	ID US 4863561	Date	Method and apparatus for cleaning integrated circuit wafers	134/1.2	XRef 134/1; 134/102.1; 156/345.3 6; 156/345.5 2; 204/192.3 2; 204/298.3 3; 257/E21.2 26; 257/E21.2	Inventor Freeman; Dean W. et al.
19	US 4804086 A		Transport container with an interchangeable inside container	206/710	27; 438/715; 438/727; 438/906 211/41.18; 220/371; 414/939; 414/940	
20	US 4745088 A		Vapor phase growth on semiconductor wafers	117/98	117/101; 117/102; 117/103; 117/935; 118/724; 118/730; 148/DIG.1 69; 148/DIG.5 7; 427/248.1; 427/593; 438/488; 438/778; 438/935	Yosuke et al.

	Document	Issue	Title	Current		Inventor
	ID	Date	Tiue	OR	XRef	Inventor
12	US 4728389 A	1988 0301	Particulate-free epitaxial process	117/97	П 34/11	Logar; Roger E.
22		1	Sealable transportable container having a particle filtering system	141/98	1	Parikh; Mihir et al.
23	US 4705444 A			414/222. 06	414/020;	Tullis; Barclay J. et al.

	Document ID	Issue Date	Title	Current OR	Current XRef	Inventor
24	ľ		Particle-free dockable interface for integrated circuit processing		141/383; 220/502	Tullis; Barclay J. et al.